



PCT

INTERNATIONAL PRELIMINARY EXAMINATION REPORT

(PCT Artcle 36 and Rule 70)

Applicant's or agent's file reference PCA30214/IPN	FOR FURTHER ACTION SeeNotificationofTransmittalofInternationalPreliminary Examination Report (Form PCT/IPEA/416)					
International application No. PCT/KR2003/001390	International filing date/day/mo		ty date (day/month/year) ECEMBER 2002 (17.12.2002)			
International Patent Classification (IPC) or national classification and IPC IPC7 H01L 21/205						
Applicant IBULE PHOTONICS INC. et al 2005. 3. 2 4 제일국제						
 This international preliminary examination report has been prepared by this International Preliminary Examining Authority and is transmitted to the applicant according to Article 36. This REPORT consists of a total of3 sheets, including this cover sheet. 						
This report is also accompanied by ANNEXES, i.e., sheets of the description, claims and/or drawings which have been amended and are the basis for this report and/or sheets containing rectifications made before this Authority (see Rule 70.16 and Section 607 of the Administrative Instructions under the PCT). These annexes consist of a total ofsheets.						
3. This report contains indications relating to the following items: I Basis of the report Priority III Non-establishment of opinion with regard to novelty, inventive step and industrial applicability Lack of unity of invention V Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability; citations and explanations supporting such statement VI Certain documents cited VII Certain defects in the international application VIII Certain observations on the international application						
Date of submission of the demand 15 JULY 2004 (15.		of completion of this rep 22 MARCH 2005 (2				
Name and mailing address of the IPEA/KR Korean Intellectual Property Office 920 Dunsan-dong, Seo-gu, Daejeon 302-701, Republic of Korea Facsimile No. 82-42-472-7140		orized officer LEE, Yoon Jik ohone No. 82-42-481-57				

l.	Basis	of the report					
1.	With	regard to the elements of the international application:*					
	\boxtimes	the international application as originally filed					
		the description:					
		pages	, as originally filed , filed with the demand				
		pages, filed with the letter of	, med widi die demaid				
		the claims:	·				
	Ш	pages	_ , as originally filed				
		pages, as amended (together with an	y statment) under Article 19				
		pages, filed with the letter of	, filed with the demand				
							
	Ш	the drawings: pages	, as originally filed				
		pages	- ·				
		pages filed with the letter of					
		the sequence listing part of the description:					
		pages					
		pages, filed with the letter of	, med with the demand				
2.	the i	n regard to the language, all the elements marked above were available or furnished to this Auth international application was filed, unless otherwise indicated under this item. se elements were available or furnished to this Authority in the following language	ority in the language in which which is				
		the language of a translation furnished for the purposes of international search (under Rule 23	· · · · · · · · · · · · · · · · · · ·				
	\vdash		. I(U)).				
		the language of publication of the international application (under Rule 48.3(b)).	in ation (and an Dalor 55 3 and /				
	Ш	the language of the translation furnished for the purposes of international preliminary examinary or 55.3).	madon(under Rules 33.2 and				
3.		With regard to any nucleotide and/or amino acid sequence disclosed in the international application, the international preliminary examination was carried out on the basis of the sequence listing:					
		contained in the international application in written form.					
		filed together with the international application in computer readable form.					
		furnished subsequently to this Authority in written form.					
		furnished subsequently to this Authority in computer readable form					
	$\overline{\Box}$	The statement that the subsequently furnished written sequence listing does not go be	yond the disc losure in the				
	_	international applicationas as filed has been furinshed.					
		The statement that the information recorded in computer readable form is identical to the vibeen furnished.	written sequence listing has				
4.		The amendments have resulted in the cancellation of:					
		the description, pages					
		the claims, Nos.					
		the drawings, sheets					
5.	_						
	Ш	This report has been established as if (some of) the amendments had not been made, sinc go beyond the disclosure as filed, as indicated in the Supplemental Box(Rule 70.2(c)).**	te they have been considered to				
*	in thi	acement sheets which have been furnished to the receiving Office in response to an invitation un s opinion as "originally filed." and are not annexed to this report since they do not contain 10.17).					
**	Any	replacement sheet containing such amendments must be referred to under item I and annexed to	o this report.				
1							

٧.	Reasoned statement under Article 35(2) with regard to novelty, inventive step or industrial applicability;
	citations and explanations supporting such statement

Statement			
Novelty (N)	Claims	1-13	YES
	Claims		<u>N</u> O
Inventive step (IS)	Claims	1-13	YES
	Claims		NO
Industrial applicability (IA)	Claims	1-13	YES
	Claims		NO
	Inventive step (IS)	Novelty (N) Claims Claims Inventive step (IS) Claims Claims Claims Claims	Novelty (N) Claims Claims Inventive step (IS) Claims Claims Industrial applicability (IA) Claims 1-13 1-13 1-13

2. Citations and explanations (Rule 70.7)

Reference is made to the following documents from the International Search Report (ISR).

D1: JP 12-068455 A D2: JP 09-186376 A D3: US 6054331 B D4: KR 1998-80778 A

D1 discloses a method for obtaining a high dielectric constant capacitor, which comprises a thermal oxide film formed on the surface of a Si single-crystal (111) plane substrate, a Ta film formed thereon as an adhesive layer, a Ti-doped WN film formed via the adhesive layer as a lower electrode layer of a ferroelectric capacitor, a ferroelectric thin film PZT formed thereon, and a Ti-doped WN film formed on the ferroelectric thin film as an upper layer of the ferroelectric capacitor.

D2 discloses a thin film of ferroelectric crystal containing Bi, Ti and O as constitutive elements which can attain a high residual spontaneous polarization by shifting the compositional ratio of Bi/Ti from stoichiometric composition.

D3 discloses an apparatus and methods of depositing a platinum film which is used as a bottom electrode for a capacitor in a DRAM cell or a non-volatile ferroelectric memory cell. The platinum film is formed in two separate processes, wherein a first thickness platinum part thereof is deposited under an inert gas atmosphere, and the second thickness platinum part is deposited under an atmosphere containing oxygen, nitrogen and/or a mixture thereof as well as an inert gas. The platinum film is annealed under a vacuum atmosphere to remove the oxygen and/or nitrogen introduced during the deposition of the second thickness platinum part.

D4 discloses a manufacturing method of a high-quality SOI wafer which is excellent in controllability, productivity and economics.

Claims 1 to 13 of the present invention relate to a ferroelectric single crystal film structure and its preparing method, which comprises adhering a ferroelectric single crystal plate to a substrate by a conductive adhesive or metal layer.

Document D1-D4 do not disclose a ferroelectric 'single crystal' structure. Therefore the novelty and the inventive step of the subject matter of the claims 1-13 is acknowledged.

The industrial applicability of the subject matter claimed in claims 1-13 is self-evident.